

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

*In re* application of:

**Yoshihide Senzaki, et al.**

Serial No.     **10/524,980**

Filed:           **March 22, 2006**

For:     **Low Temperature Deposition of  
Silicon Oxides and Oxynitrides**

Examiner:   **Lee, Hsien Ming**

Art Unit:     **2823**

Confirmation No.: **3254**

Atty. Docket No.: **067538-5172-US**

Date:     **March 25, 2008**

**RESPONSE/AMENDMENT**

Mail Stop AMENDMENT  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the non-final Office Action mailed September 25, 2007, please consider the following proposed amendments to the above-identified application and the remarks herein. Please amend the application as follows. Accompanying this Response is a petition for extension of time, with requisite fee, to bring the period of response to March 25, 2008.

**Amendments to the Specification** begins on page 2 of this Amendment.

**Amendments to the Claims** begin on page 4 of this Amendment.

**Remarks** begin on page 9 of this Amendment.